

iMiD 2015 Display Special Exhibition

Materials, Components and Instrument

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Exhibitor Introduction (Within 200 words)	<p>CN1 Co. Ltd. is a semiconductor and high-tech equipment manufacturing company located in Hwaseong, Gyeonggi province, near Samsung Semiconductor Company. We have tried our best to provide better service based on many years of experience and technology.</p> <p>We are doing our best rather than being the best with trust, sincerity and responsibility.</p> <p>Contact us anytime for enquiries.</p>
Exhibit Description (Within 200 words)	<p>Atomic Layer Deposition (ALD) is a coating method to fabricate thin films on various substrates with atomic scale precision. Similar in chemistry to Chemical Vapor Deposition (CVD), except that the ALD reaction breaks the CVD reaction into two half-reactions, keeping the precursor materials separate during the reaction.</p> <p>ALD film growth is self-limited and based on surface reaction, which makes achieving atomic scale deposition control possible. By keeping the precursors separate throughout the coating process, atomic-level thickness control of film grown can be obtained as fine as atomic/molecular scale per monolayer.</p>
Exhibit Product	<ol style="list-style-type: none"> 1. Atomic Premium (ALD/PE-ALD/CVD/PE-CVD) <ul style="list-style-type: none"> - Shower-head type Plasma-Enhanced Atomic Layer Deposition 2. Atomic Classic <ul style="list-style-type: none"> - Traveling-wave type Atomic Layer Deposition 3. Atomic Shell <ul style="list-style-type: none"> - Atomic Layer Deposition with rotation reactor for coating shell layer on powders
Company logo	